Charge Deposition and Collection in HV-MAPS



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High Voltage - Monolithic Active Pixel Sensors (HV-MAPS)

• Monolithic: Readout and active volume on same chip



[I.Peric, P. Fischer et al., NIM A 582 (2007) 876]

Characteristics:

- Diode realised as deep n-well in psubstrate reversly biased up to -140 V
- $\rightarrow w \propto \sqrt{\rho U}$
- Fast charge collection via drift in depleted volume

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Charge Deposition and Collection in HV-MAPS

- Traversing particle creates e-h pairs
- Fast charge in depleted volume collected via drift
- Diffusion in non depleted volume
- $\sigma = \sqrt{2Dt}$

Time [ns]	Gaussian spread σ [μm]
500	62 ± 2.4
750	75 ± 3
1000	87 ± 3

→How large is the contribution from diffusion?



[H. Augustin doi:10.11588/heidok.00030885, modified]

HV-MAPS Roadmap



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Run2021V2

- Small scale (5 \times 5 mm²) R&D sensor
- In-pixel electronics contain amplifier and CMOS comparator
- \rightarrow Best possible sensor architecture

→Following results focus on: d=50 µm, 100 µm, 600 µm; $\rho = 370 \Omega cm$



Substrate [Ωcm]	20, 370 , ~8000	
Thickness [µm]	50, 100, 300, 600	
Matrix [Pixel]	29x124	
Pixel size[µm²]	165x25	
Sensor size [mm ²]	5x5	

Prototype Performance: Efficiency and Time Resolution

- 100 μ m, source: 4 GeV e⁻ beam
- Efficiency > 99%, average noise < 0.1 Hz/pixel
- With 8 ns binning and without corrections: $\sigma_t < 2.4$ ns



Measurement Setup

- Study charge collection by varying HV with various signal sources
- Compare ToT & Cluster size of DUTs at same configuration & HV
- 90 Sr: 2.28 MeV e⁻ source \rightarrow continous spectrum
- ⁵⁵Fe : Monochromatic x-ray source 5.9 keV
- Testbeam@DESY: 4 GeV electrons



$w \propto \sqrt{\rho U}$				
High Voltage [-V]	Approx. Depletion Depth			
	(ρ= 370 Ωcm) [μm]			
20	30			
80	60			
130	~75			

Cluster Size and ToT Spectra of ⁹⁰Sr



- 50 µm sensor completly depleted
 →No diffusive contribution to signal
- Thicker chip → higher ToT, larger average cluster size

Chip	Depletion	oletion Undepleted	
Thickness	Depth[µm]	Substrate [µm]	
50	30	~0	
100	30	50	
600	30	550	

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Testbeam: Clustersize and TOT 50 μm vs 100 μm

- 4 GeV electron beam, both sensors at same configuration
- Higher ToT/ cluster size for 100 μm Chip
- \rightarrow Diffusion of charges into depleted volume



⁵⁵Fe Spectrum - Single Pixel vs Full Chip

- ⁵⁵Fe : Monochromatic x-ray source 5.9 keV
- Full chip ToT vs (random) single pixels ToT
- \rightarrow Pixel response varies
- \rightarrow Calibration necessary





Energy Resolution



- Use ⁵⁵Fe single pixel ToT
- Not considered: Charge sharing, second peak (6.5 keV)
- Assume linearity ToT to Energy

•
$$\frac{\sigma_E}{E} = 0.106$$

• Energy resolution (FWHM):

$$\frac{\Delta E}{E} = 0.250$$

Summary & Outlook

- ToT/ cluster size increases with thickness (testbeam & laboratory)
- → Diffusion considerably increases signal and cluster size for small depletion depth
- Single Pixel: $\frac{\sigma_E}{E} = 0.106$ (at 5.9 keV)
- Pixel response varies \rightarrow to compare two pixels calibration needed \rightarrow ⁵⁵Fe

- →Outlook: Compare calibrated sensors with different thicknesses
- Compare measurements with Allpix² simulation



Backup



⁵⁵Fe Spectrum – HV Dependence

- ⁵⁵Fe signal in dependence of HV
- Only small shifts visible
- →No large contribution by diffusion: 5.9 keV e⁻ is absorbed in depleted zone
- Difference in signal by decreasing pixel capacitance





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Voltage Measurements Run 2021 v2, $ho=20~\Omega { m cm}$

160

- HV applied at Pixel Guard Ring, measured at Chip Guard Ring
- Voltage at Chip Guard Ring follows exactly





Side View

Crosssection

HV-pixel

Voltage Measurements, $ho = 370~\Omega cm$

- HV via Chip Guard Ring → Measured voltage at Pixel Guard Ring is lower
- At breakdown voltage ~ 91 V measured at Pixel Guard Ring





ToT Spectra of ⁹⁰Sr

- HV= -130 V: ~75 μm depletion depth
- \rightarrow Larger signal from drift
- \rightarrow Amplifier reaches saturation
- Only small diffusive contribution to signal at HV = -130 V



Chip to Chip Comparison 600 μm

• All sensors on same settings



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Injection Calibration to Fe55





Desy Testbeam

- Telescope consisting of 3 reference Layers (MuPix11) + DUT
- DUT: Run 2021v2; 300 μm (ρ = ~8000 Ωcm),
 100 μm and **50 μm** (ρ = 370 Ωcm)
- Threshold scans and high statistic runs at different HVs
- Focus: Compare DUTs at same settings & HV





Power Consumption Run2021

	VDD	VDDA
Power consumption on default settings (measured)	90.18 mW	88.02 mW
Minimal power consumption:	1.44 mW	2.88 mW
Scaling with pixel #: Pixel, Periphery	0.35 μW/Pixel	16.9 μW/Pixel
Total Power Consumption	1.26 mW	60.84 mW
Power comsumption per active area	/	410.15 mW/cm ²
Scaling with chip #: Link, Clock	88.92 mW/Chip	27.38 mW/Chip

- MuPix10: Power consumption per active area: ~200 mW/cm²
- Run2021 has half the pixel size

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